

# Photoresist Patterning of Round Substrates

APPLICATIONS  
NOTE #708



*Photoresist Pattern  
on Internal Surface  
of Round Substrate.  
(Diameter=3 cm)*



*Photoresist Pattern on  
External Surface of  
Nickel Plated Substrate.*



*Magnified View (10X)  
of Photoresist Pattern  
on Nickel Plated  
Round Substrate.*

## Overview:

Standard positive photoresist is used to pattern highly curved, round substrates with the SF-100.

## Process Flow:

1. Start with round substrate.
2. Coat with positive photoresist.
3. Expose patterns on the SF-100.
4. Develop photoresist.



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